



Fig. 4 (a) INPUT

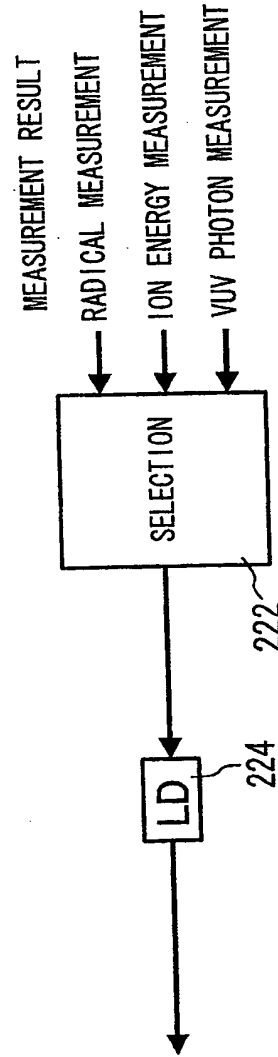
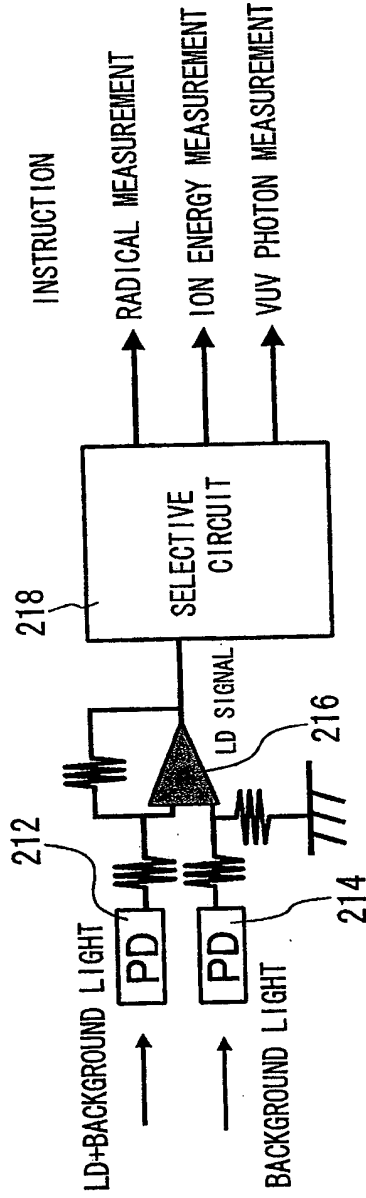


Fig. 4 (b) OUTPUT

STRUCTURE OF ON-WAFER ION ENERGY ANALYZER

Fig. 7 (a)

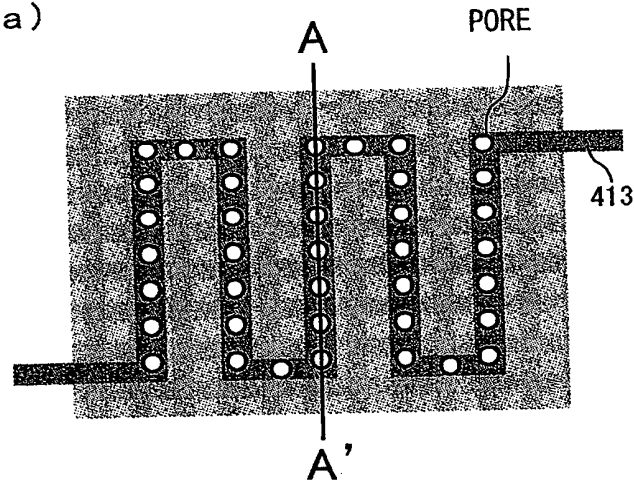


Fig. 7 (b)

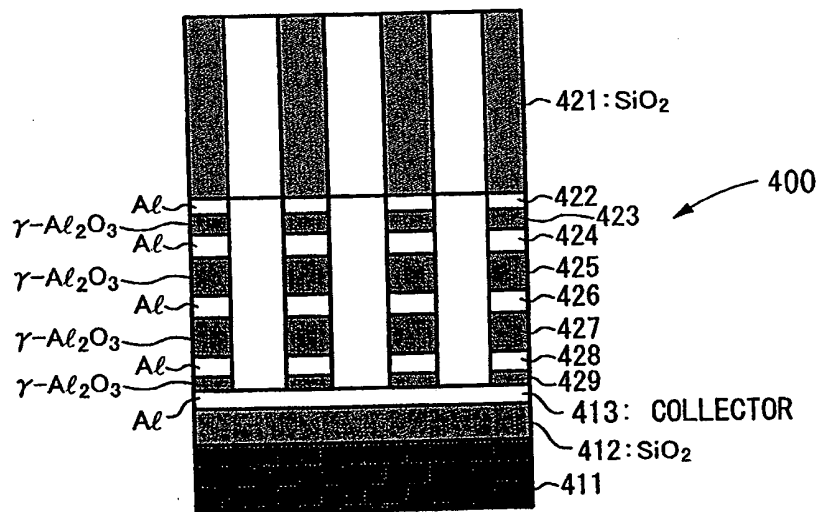
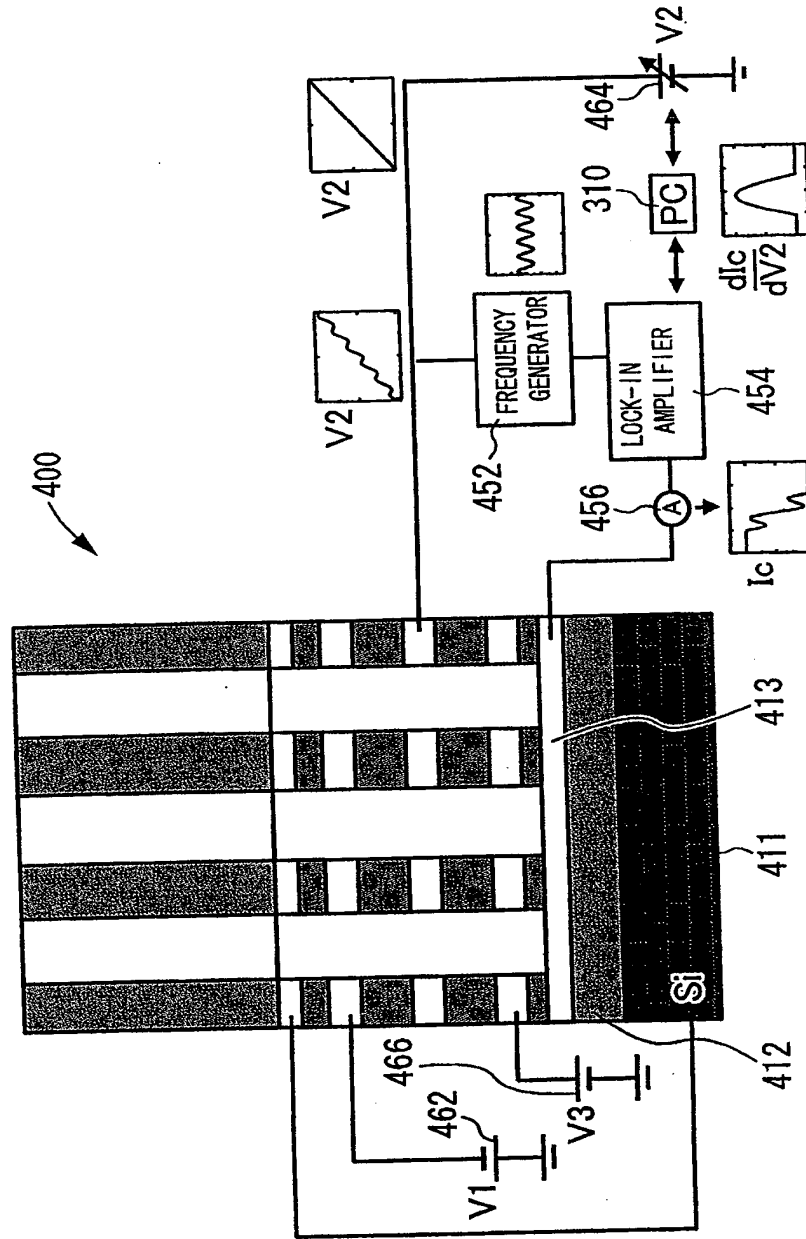


Fig. 8 MEASUREMENT SYSTEM OF ON-WAFER ION ENERGY ANALYZER



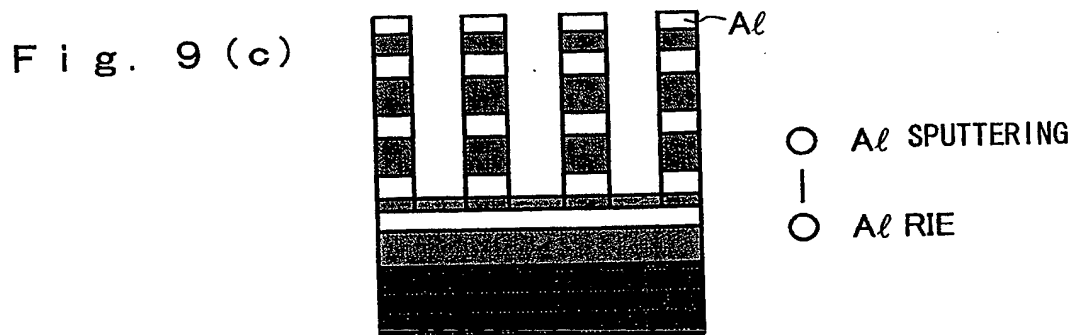
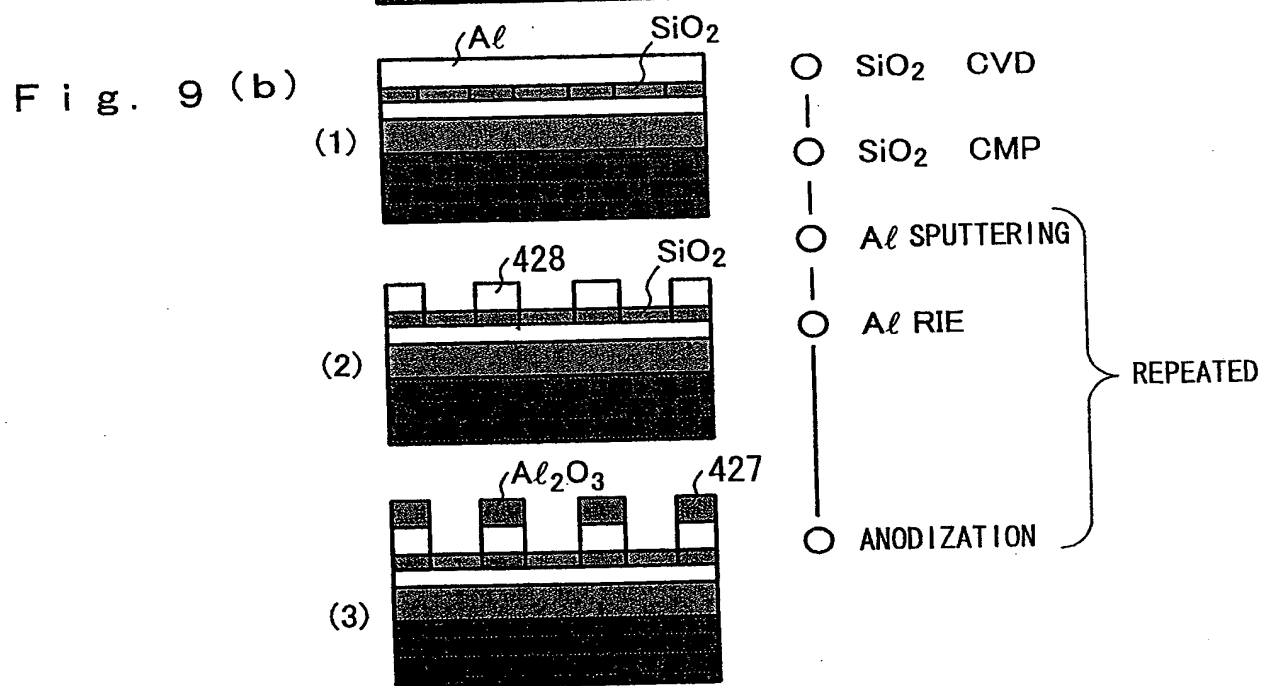
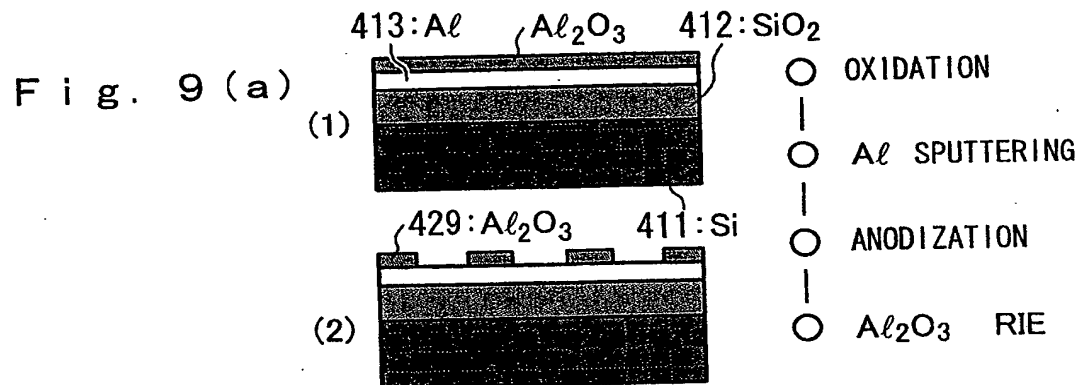


Fig. 10(d)

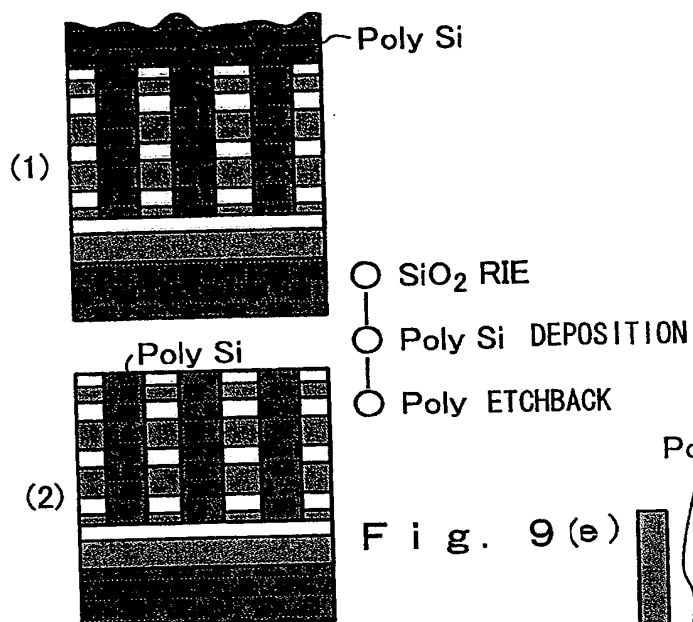


Fig. 9(e)

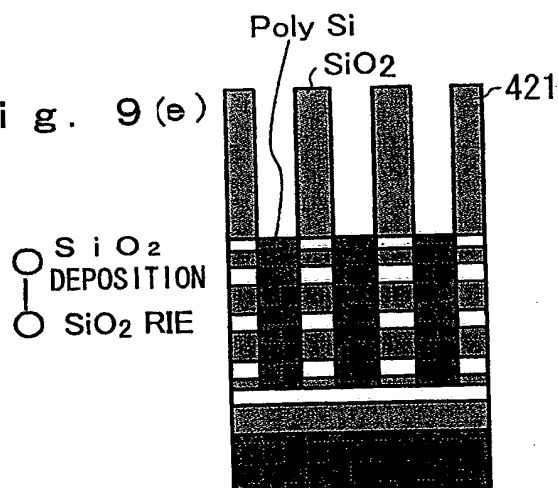
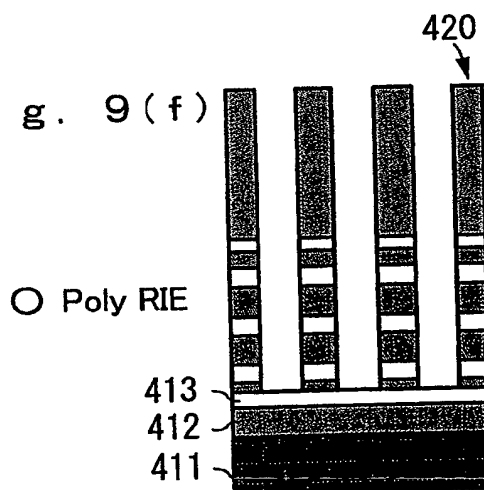


Fig. 9(f)



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Fig. 11(a)

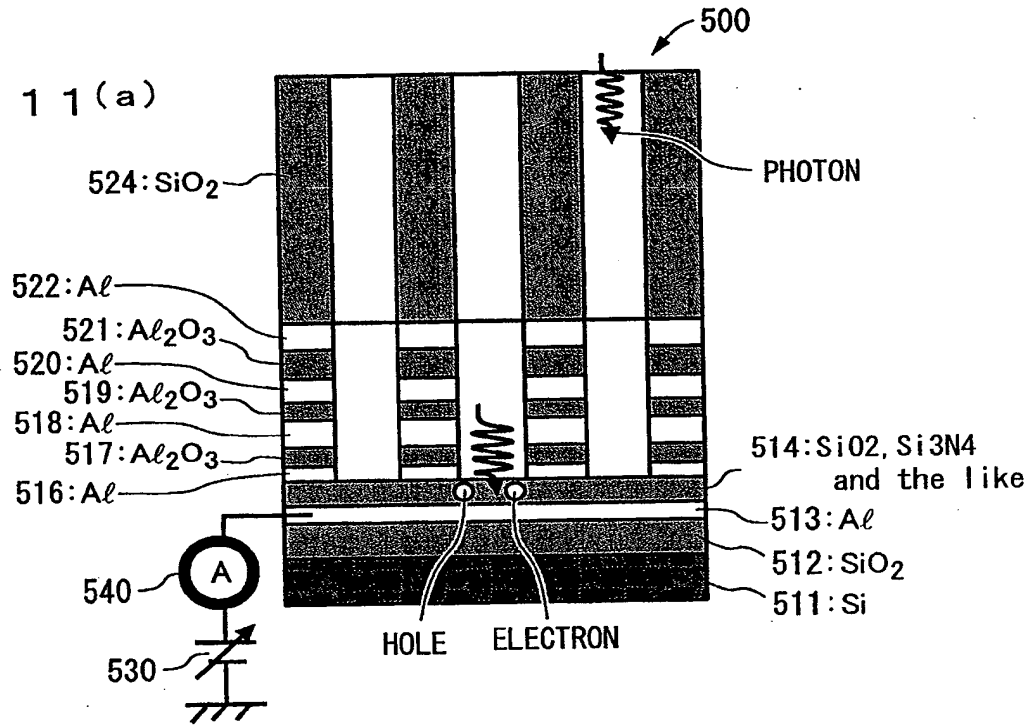
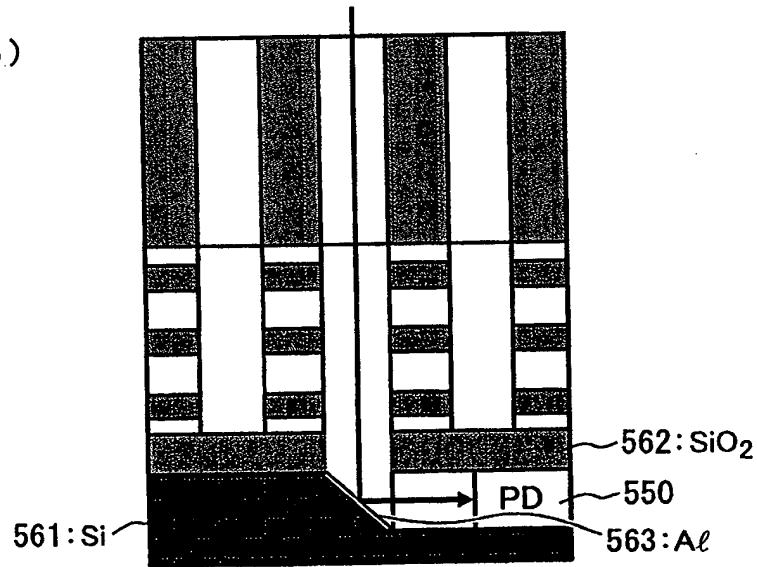


Fig. 11(b)



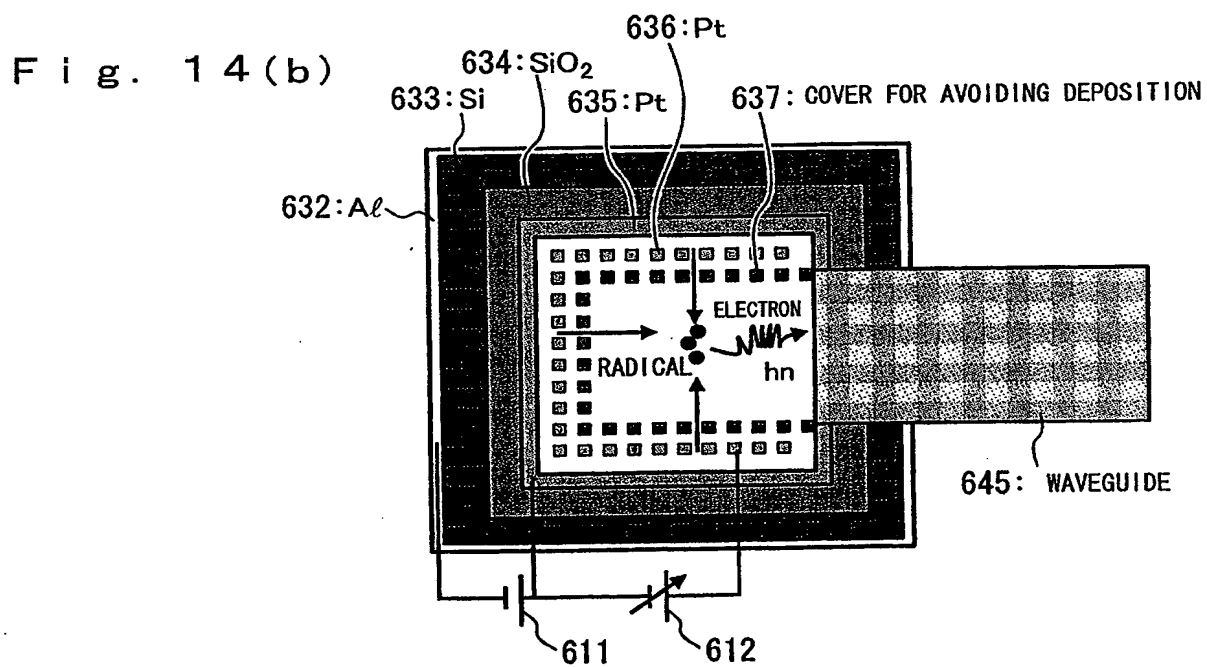
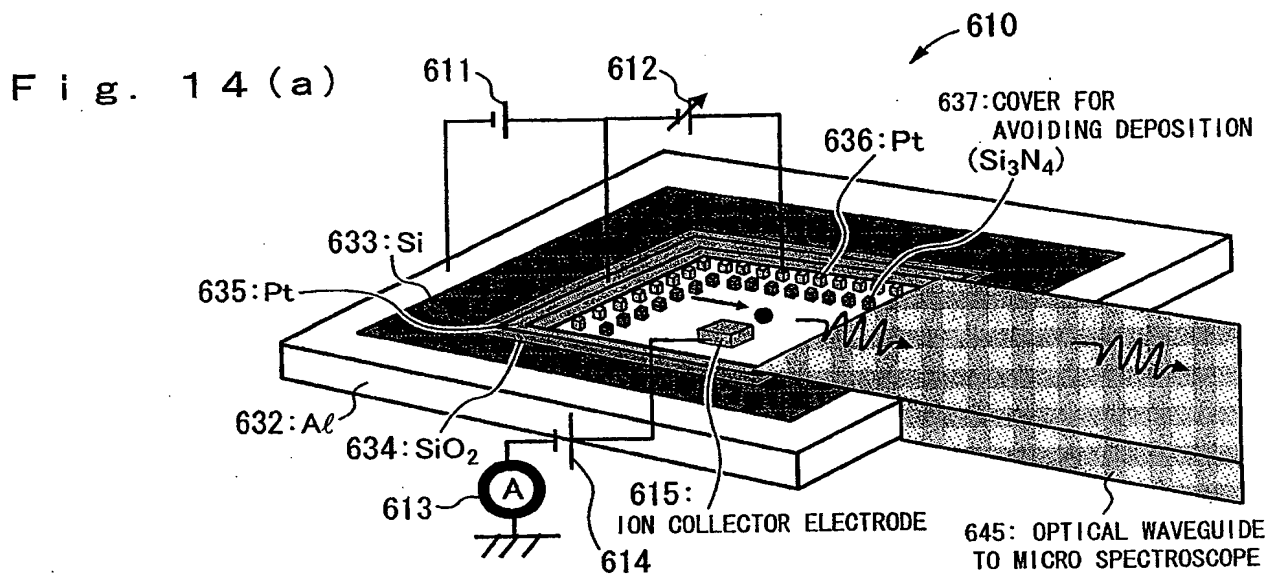


Fig. 15

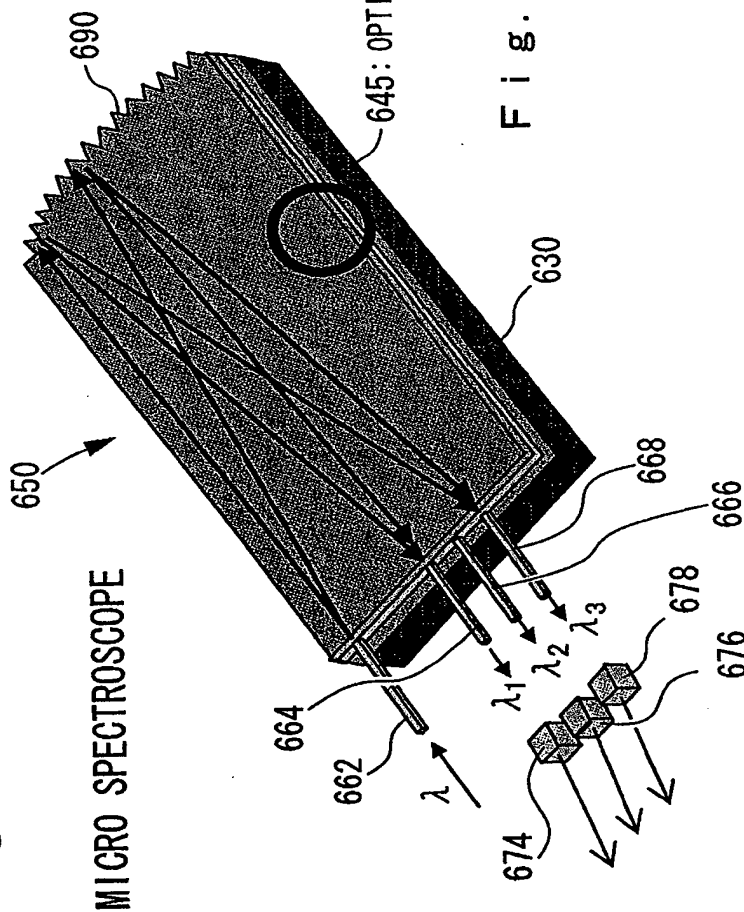


Fig. 15(a)

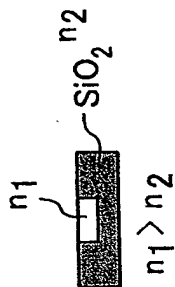
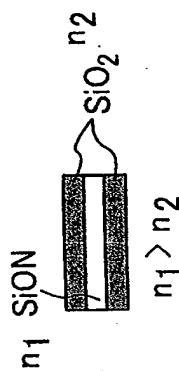


Fig. 15(b)



MANUFACTURING PROCESS OF MICRO ION RADICAL ANALYZER (1)

Fig. 16(a) OXIDATION



Fig. 16(b) Si DEPOSITION, ETCHING



Fig. 16(c) Al VAPOR DEPOSITION, ETCHING



Fig. 16(d) SiO₂ DEPOSITION, ETCHING



Fig. 16(e) Pt DEPOSITION, PATTERNING

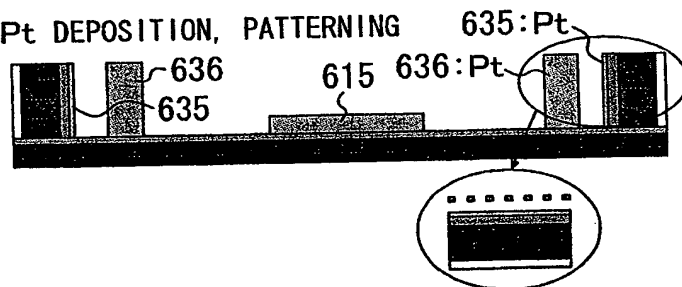


Fig. 16(f) Si₃N₄ DEPOSITION, ETCHING

